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APPLICATION NO. FILING DATE FIRST NAMED INVENTOR ATTORNEY DIX: KET NO. CONFIRMATION NO. 09/692,007 10/19/2000 TEGL1082US1 SRM 7175 Stephen P. DeOrnelfas

23910

7590

11/26/2003

FLIESLER DUBB MEYER & LOVEJOY, LLP FOUR EMBARCADERO CENTER SUITE 400 SAN FRANCISCO, CA 94111

EXAMINER

UMEZ ERONINI, LYNETTE T ART UNIT PAPER NUMBER

1765

DATE MAILED: 11/26/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

		AS
Application No.	Applicant(s)	1
09/692,007	DEORNELLAS ET AL.	
Examiner	Art Unit	
Lynette T. Umez-Eronini	1765	

Advisory Action

--The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

THE REPLY FILED 03 November 2003 FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE. Therefore, further action by the applicant is required to avoid abandonment of this application. A proper reply to a C(

final rejection under 37 CFR 1.113 may only be either: (1) a timely filed amendmen condition for allowance; (2) a timely filed Notice of Appeal (with appeal fee); or (3) a Examination (RCE) in compliance with 37 CFR 1.114.	t which places the application in a timely filed Request for Continued
PERIOD FOR REPLY [check either a) or b)]	
a) The period for reply expiresmonths from the mailing date of the final rejection.	
b) The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set fort event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS FILED WITHIN TWO MONTHS C 706.07(f).	date of the final rejection. OF THE FINAL REJECTION. See MPEP
Extensions of time may be obtained under 37 CFR 1.136(a). The date on which the petition under 37 CI have been filed is the date for purposes of determining the period of extension and the corresponding amount 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened statutory period for reply originally (b) above, if checked. Any reply received by the Office later than three months after the mailing date of the fir earned patent term adjustment. See 37 CFR 1.704(b).	t of the fee. The appropriate extension fee under set in the final Office action; or (2) as set forth in
1. A Notice of Appeal was filed on Appellant's Brief must be filed within 37 CFR 1.192(a), or any extension thereof (37 CFR 1.191(d)), to avoid dismi	
2. The proposed amendment(s) will not be entered because:	
(a) X they raise new issues that would require further consideration and/or sea	arch (see NOTE below);
(b) they raise the issue of new matter (see Note below);	
(c) they are not deemed to place the application in better form for appeal by issues for appeal; and/or	materially reducing or simplifying the
(d) \square they present additional claims without canceling a corresponding number	er of finally rejected claims.
NOTE: <u>See Continuation Sheet</u> .	
3. Applicant's reply has overcome the following rejection(s):	
4. Newly proposed or amended claim(s) would be allowable if submitted i canceling the non-allowable claim(s).	n a separate, timely filed amendment
5. ☐ The a) ☐ affidavit, b) ☐ exhibit, or c) ☐ request for reconsideration has been application in condition for allowance because: <u>See Continuation Sheet</u> .	considered but does NOT place the
6. The affidavit or exhibit will NOT be considered because it is not directed SOL raised by the Examiner in the final rejection.	LELY to issues which were newly
7. For purposes of Appeal, the proposed amendment(s) a) will not be entered explanation of how the new or amended claims would be rejected is provided	
The status of the claim(s) is (or will be) as follows:	
Claim(s) allowed: none.	
Claim(s) objected to: none.	
Claim(s) rejected: <u>10-49</u> .	
Claim(s) withdrawn from consideration: <u>1-9</u> .	
8. \square The drawing correction filed on is a) \square approved or b) \square disapprove	d by the Examiner.
9. Note the attached Information Disclosure Statement(s)(PTO-1449) Paper No.	o(s)
10. Other:	NADINE G. NORTON
SUP	PRIMARY EXAMINER
	Hal /h

U.S. Patent and Trademark Office PTOL-303 (Rev. 11-03)

Continuation Sheet (PTOL-303)

Application No.

Continuation of 2. NOTE: In (New) Claim 50, "The method of claim 10, wherein the hard mask is deposited over the layer to be etched without being deposited on side walls of the layer to be etched" and In (New) Claim 51, "The method of claim 11, further comprising the step of: oxidizing the hard mask either prior to or during heating by exposing the hard mask to a stream of oxidizing gas' raise new issues that would require further consideration.

Continuation of 5, does NOT place the application in condition for allowance because:

applicant's argument that the motivation for combining Fullowan with Moslehi's method of providing energy to the reactor would not be obvious due to increase processing time and which differs from the Examiner's reason for combining the reference is unpersuasive, the fact that applicant has recognized another advantage which would flow naturally from following the suggestion of the prior art cannot be the basis for patentability when the differences would otherwise be obvious. See Ex parte Obiaya, 227 USPQ 58, 60 (Bd. Pat. App. & Inter. 1985); and

applicant's argument that neither Fullowan nor Moslehi are believed to disclose introducing a stream of oxidizing gas to enhance the oxidation process is unpersuasive because Fullowan teaches, masking a tungsten layer with a titanium mask (column 2, lines 39-40), etching the mask workpiece to selectively remove the unmasked tungsten (column 2, lines 55-57) and by reactive ion etching using CF4/O2 (same as applicant's stream of oxidizing gas) mixture (column 2, lines 57-68). Since Fullowan uses the same etchants in exposing the same mask materials as those of the present invention, then using Fullowan's method of exposing the hard mask layer with the etchant, in the same manner as the claimed invention would inherently result to increase the oxidation rate of the hard mask to slow erosion.